



Attorney's Docket No.: 10559-882001/P17484
Intel Corporation

Ifw

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Yan Borodovsky
Serial No.: 10/693,373
Filed : October 24, 2003
Assignee : Intel Corporation
Title : COMPOSITE OPTICAL LITHOGRAPHY METHOD FOR PATTERNING
LINES OF UNEQUAL WIDTH

Art Unit: 1756
Examiner:

Mail Stop Amendment

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants call attention to the attached Information Disclosure Statement and documents listed on form PTO-1449.

This filing is being made before the receipt of a first Office action on the merits. No fee is required.

The documents are in the English language; hence no concise explanation is necessary per Rule 98(a)(3).

Consideration of the foregoing and enclosures plus the return of a copy of the enclosed form PTO-1449 with the

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37 CFR §1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

March 29, 2005

Date of Deposit

Signature

Jennifer H. Payne

Typed or Printed Name of Person Signing Certificate

Applicant : Yan Borodovsky
Serial No.: 10/693,373
Filed : October 24, 2003
Page 2 of 2

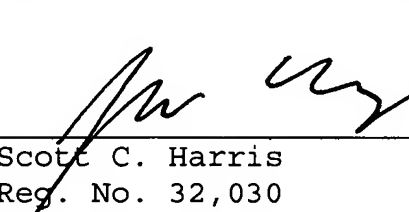
Attorney's Docket No.:10559-882001

Examiner's initials in the left column per MPEP 609 are
earnestly solicited along with an early action on the merits.

Please apply any additional charges or credits to Deposit
Account No. 06-1050.

Respectfully submitted,

Date: March 29, 2005



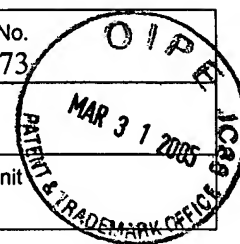
Scott C. Harris
Reg. No. 32,030
Attorney for Intel Corporation

John F. Conroy
Reg # 45,485

Fish & Richardson P.C.
USPTO Customer No. **20985**
12390 El Camino Real
San Diego, CA 92130
Telephone: (858) 678-5070
Facsimile: (858) 678-5099

10497431.doc

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-882001	Application No. 10/693,373
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Yan Borodovsky	
		Filing Date October 24, 2003	Group Art Unit 1756



U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AE							
	AF							
	AG							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AH	M. Fritze, et al., "Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography", <i>J. of Vacuum Science & Technology B</i> , 19(6):2366-2370, Nov/Dec 2001.
	AI	J.A. Hoffnagle, et al., "Liquid immersion deep-ultraviolet interferometric lithography", <i>J. of Vacuum Science & Technology B</i> , 17(6):3306-3309, Nov/Dec 1999.
	AJ	Marc D. Levenson, et al., "Exposing the DUV SCAAM - 75 nm Imaging on the Cheap!", <i>Proc. of SPIE: Design, Process Integration, and Characterization for Microelectronics</i> , 4692:288-297, March 2002.
	AK	Alex K. Raub, et al., "Deep UV immersion interferometric lithography", <i>Proc. of SPIE: Optical Microlithography XVI</i> , 5040:667-678, Feb. 2003.
	AL	Bruce W. Smith, et al., "Water immersion optical lithography at 193 nm", <i>J. Microlith., Microfab., Microsyst.</i> , 3(1):44-51, Jan. 2004.
	AM	Akiyoshi Susuki, et al., "Multilevel imaging system realizing $k_1 \pm 0.3$ lithography", <i>Proc. of SPIE: Optical Microlithography XII</i> , 3679:396-407, Mar. 1999.
	AN	M. Switkes, et al., "Extending optics to 50 nm and beyond with immersion lithography", <i>J. of Vacuum Science & Technology B</i> , 21(6):2794-2799, Nov/Dec 2003.
	AO	Brian Tyrrell, et al., "Investigation of the physical and practical limits of dense-only phase shift lithography for circuit feature definition", <i>J. Microlith., Microfab., Microsyst.</i> , 1(3):244-252, Oct. 2002.
	AP	Saleem H. Zaidi, et al., "Multiple exposure interferometric lithography", <i>Proc. of SPIE: Optical Microlithography VII</i> , 2197:869-875, Mar. 1994.
	AQ	M. Fritze, et al., "Preprint of poster presentation entitled "High-Throughput Hybrid Optical Maskless Lithography: All-Optical 32-nm Node Imaging," Presented at SPIE Microlithography 2005, San Jose, California, USA, March 3, 2005.

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	